

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	2	((first with spacer) and (second with spacer) and (silicon with oxide) and polysilicon and (anisotropic with etch\$3) and selective and silicide and sidewall).CLM.	US-PGPUB	OR	ON	2005/10/13 15:52
L3	13	((first with spacer) and (spacer with silicon with oxide) and polysilicon and etch\$3 and selective and sidewall).CLM.	US-PGPUB	OR	ON	2005/10/13 15:51
L4	10	((first with spacer) and (second with spacer) and ((silicon with oxide) or dielectric) and polysilicon and (anisotropic with etch\$3) and selective and (silicide or (metal with semiconductor)) and source and drain).CLM.	US-PGPUB	OR	ON	2005/10/13 15:55
L5	10	((first with spacer) and (second with spacer) and ((silicon with oxide) or dielectric) and polysilicon and (anisotropic with etch\$3) and selective and (silicide or (metal with semiconductor)) and source and drain and (silicon with nitride)).CLM.	US-PGPUB	OR	ON	2005/10/13 15:56